ABSTRACT

A highly reliable plated lead finishing structure for a semiconductor part using a Pd film or a Pd alloy 5 film, instead of a traditional solder plating material, as a brazing metal, without causing a problem of shortcircuits between terminals due to whiskers, is provided. In the plated lead finishing structure of the invention, when a plated film having a thickness of not larger than 1.0 0.3 µm is formed using Pd or a Pd alloy (26), instead of a conventional solder-plating material as a brazing metal, on the surfaces of the external connection terminals (10, 12) of a semiconductor part using copper or a copper alloy-based material, the film is plated 15 without interposing any underlying layer or any intermediate metal layer between the material and the Pdor Pd alloy-plated layer. In some cases, Au or an Au alloy (28) is further plated and has a thickness of not larger than 0.1 µm on the plated film.